

# Fabrication of n<sup>+</sup>-poly-Si/p<sup>+</sup>-c-Si tunnel diode using Low-pressure Chemical Vapor Deposition for Photovoltaic Applications

Vineet Kumar Singh\* 

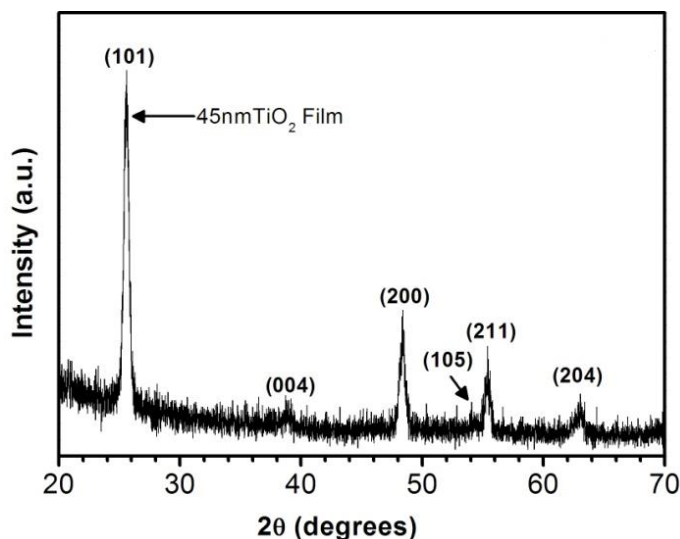


Fig. S1. Grazing incident X-ray diffraction (GIXRD) pattern of TiO<sub>2</sub> film.

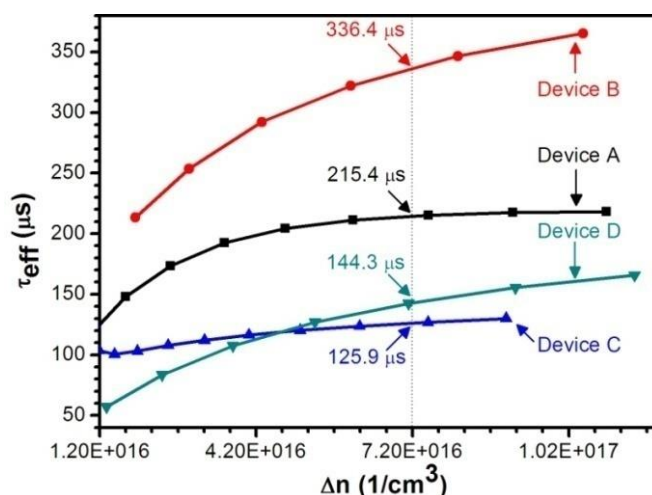


Fig. S2 Effective minority carrier recombination life time dependence on excess electron concentration (Δn) at λ=980 nm and 85 mW laser power.

Department of Physics, DDU Gorakhpur University, Gorakhpur-273009, India  
 \*Corresponding author: E-mail: 1vineetkumarsingh@gmail.com

DOI: 10.5185/amlett.2022.021693